

WHAT IS CLAIMED IS:

1. An electron optical system array having a plurality of electron lenses, comprising:

5 a plurality of electrodes arranged along paths of a plurality of charged-particle beams,

wherein each of said plurality of electrodes has a membrane in which a plurality of apertures are formed on the paths of the plurality of charged-particle beams,
10 and a support portion which supports the membrane, and at least two of said plurality of electrodes are arranged to form a nested structure.

2. The array according to claim 1, wherein the electron optical system array further
15 comprises a base member, and

the support portions of said at least two electrodes which form the nested structure are supported by said base member.

3. The array according to claim 2, wherein the
20 support portions of said at least two electrodes which form the nested structure are supported by one surface of said base member.

4. The array according to claim 1, wherein all said plurality of electrodes are arranged to form a nested
25 structure.

5. The array according to claim 4, wherein the electron optical system array further

comprises a base member, and

the support portions of all said plurality of electrodes are supported by said base member.

6. The array according to claim 5, wherein the
5 support portions of all said plurality of electrodes are supported by one surface of said base member.

7. The array according to claim 1, wherein said plurality of electrodes are arranged to form at least two nested structures.

10 8. The array according to claim 7, wherein the electron optical system array further comprises a base member having first and second surfaces, and

said base member supports one of the at least two
15 nested structures by the first surface and supports the other one of the at least two nested structures by the second surface.

9. The array according to claim 7, further comprising at least two base members which respectively
20 support the at least two nested structures.

10. The array according to claim 7, further comprising a coupling portion which couples the at least two nested structures.

11. The array according to claim 1, wherein
25 the support portions of said at least two electrodes which form the nested structure have hollow portions, and

one electrode is arranged inside the hollow portion of the other electrode.

12. The array according to claim 2, wherein one of said plurality of electrodes except for said at least two electrodes which form the nested structure faces an electrode located farthest from said base member out of said at least two electrodes which form the nested structure.

13. The array according to claim 12, wherein the support portion of one of said plurality of electrodes except for said at least two electrodes which form the nested structure is smaller in size than the support portion of said electrode located farthest from said base member out of said at least two electrodes which form the nested structure.

14. The array according to claim 1, wherein said plurality of electrodes are arranged to prevent the membranes of said plurality of electrodes from contacting each other.

15. The array according to claim 1, wherein at least one of said plurality of electrodes is divided in units of columns each formed from a plurality of apertures.

16. The array according to claim 1, wherein the number of electrodes which form the nested structure is two.

17. The array according to claim 1, wherein the number of electrodes which form the nested structure is

three.

18. The array according to claim 1, wherein

at least one of said plurality of electrodes is
an electrode for forming an electric field which acts

5 on a charged-particle beam, and

at least another one of said plurality of
electrodes is a shield electrode.

19. A method of manufacturing an electron optical
system array having a plurality of electron lenses,

10 comprising:

the preparation step of preparing a plurality of
electrodes each having a membrane in which a plurality
of apertures are formed, and a support portion which
supports the membrane;

15 the step of preparing a base member; and

the fixing step of fixing the support portions of
the plurality of electrodes to the base member so as to
form a nested structure by all or some of the plurality
of electrodes.

20 20. The method according to claim 19, wherein in the
electrode preparation step, the plurality of electrodes
are fabricated using plating.

21. A charged-particle beam exposure apparatus
comprising:

25 a charged-particle beam source for emitting a
charged-particle beam;

an electron optical system array which has a

plurality of electron lenses and forms a plurality of intermediate images of said charged-particle beam source by the plurality of electron lenses; and

5 a projection electron optical system for projecting on a substrate the plurality of intermediate images formed by said electron optical system array,

wherein said electron optical system array includes a plurality of electrodes arranged along paths of a plurality of charged-particle beams concerning the plurality of intermediate images,

10 each of said plurality of electrodes has a membrane in which a plurality of apertures are formed on the paths of the plurality of charged-particle beams, and a support portion which supports the membrane, and
15 at least two of said plurality of electrodes are arranged to form a nested structure.

22. A device manufacturing method comprising the steps of:

installing a plurality of semiconductor manufacturing apparatuses including a charged-particle beam exposure apparatus in a factory; and

manufacturing a semiconductor device by using the plurality of semiconductor manufacturing apparatuses,

25 wherein the charged-particle beam exposure apparatus includes

a charged-particle beam source for emitting a charged-particle beam,

an electron optical system array which has a plurality of electron lenses and forms a plurality of intermediate images of the charged-particle beam source by the plurality of electron lenses, and

5 a projection electron optical system for projecting on a substrate the plurality of intermediate images formed by the electron optical system array,

the electron optical system array includes a plurality of electrodes arranged along paths of a plurality of charged-particle beams concerning the
10 plurality of intermediate images,

each of the plurality of electrodes has a membrane in which a plurality of apertures are formed on the paths of the plurality of charged-particle beams,
15 and a support portion which supports the membrane, and

at least two of the plurality of electrodes are arranged to form a nested structure.

23. The method according to claim 22, further comprising the steps of:

20 connecting the plurality of semiconductor manufacturing apparatuses by a local area network;

connecting the local area network to an external network of the factory;

acquiring information about the charged-particle
25 beam exposure apparatus from a database on the external network by using the local area network and the external network; and

controlling the charged-particle beam exposure apparatus on the basis of the acquired information.

24. A semiconductor manufacturing factory comprising:
a plurality of semiconductor manufacturing

5 apparatuses including a charged-particle beam exposure apparatus;

a local area network for connecting said plurality of semiconductor manufacturing apparatuses; and

10 a gateway for connecting the local area network to an external network of said semiconductor manufacturing factory,

wherein said charged-particle beam exposure apparatus includes

15 a charged-particle beam source for emitting a charged-particle beam,

an electron optical system array which has a plurality of electron lenses and forms a plurality of intermediate images of said charged-particle beam

20 source by the plurality of electron lenses, and

a projection electron optical system for projecting on a substrate the plurality of intermediate images formed by said electron optical system array,

said electron optical system array includes a
25 plurality of electrodes arranged along paths of a plurality of charged-particle beams concerning the plurality of intermediate images,

each of said plurality of electrodes has a membrane in which a plurality of apertures are formed on the paths of the plurality of charged-particle beams, and a support portion which supports the membrane, and

5 at least two of said plurality of electrodes are
arranged to form a nested structure.

25. A maintenance method for a charged-particle beam exposure apparatus, comprising the steps of:

preparing a database for storing information
10 about maintenance of the charged-particle beam exposure
apparatus on an external network of a factory where the
charged-particle beam exposure apparatus is installed;

connecting the charged-particle beam exposure apparatus to a local area network in the factory; and

15 maintaining the charged-particle beam exposure
apparatus on the basis of the information stored in the
database by using the external network and the local
area network.

wherein the charged-particle beam exposure
 20 apparatus includes

a charged-particle beam source for emitting a charged-particle beam,

an electron optical system array which has a plurality of electron lenses and forms a plurality of intermediate images of the charged-particle beam source by the plurality of electron lenses, and

a projection electron optical system for

projecting on a substrate the plurality of intermediate images formed by the electron optical system array,

the electron optical system array includes a plurality of electrodes arranged along paths of a
5 plurality of charged-particle beams concerning the plurality of intermediate images,

each of the plurality of electrodes has a membrane in which a plurality of apertures are formed on the paths of the plurality of charged-particle beams,
10 and a support portion which supports the membrane, and

at least two of the plurality of electrodes are arranged to form a nested structure.